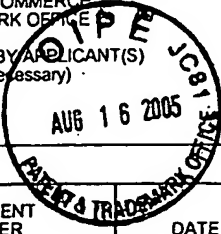


FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		ATTY DOCKET NO. 03500.017112		APPLICATION NO. 10/653,978			
		APPLICANT Kazuhiko Fukutani et al.					
		FILING DATE September 4, 2003		GROUP 1775			
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
LX		6,610,463 B1	08/26/03	Ohkura et al.	430	322	08/29/00
		2004/0001964 A1	01/01/04	Ohkura et al.	428	596	08/29/00
		2001/0036563 A1	11/01/01	Watanabe et al.	428	694T	
		2002/0031008 A1	03/14/02	Den et al.	365	173	
		2002/0086185 A1	07/04/02	Yasui et al.	428	694TS	
		2004/0048092 A1	03/11/04	Yasui et al.	428	642	
		6,602,620 B1	08/05/03	Kikitsu et al.	428	694T	
		2005/0053773 A1	03/10/05	Fukutani et al.	428	209	08/06/04
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
LX	JP	2001-273622	10/05/01	Japan			Abstract
	JP	52-78403	07/01/77	Japan			No
	JP	62-270473	11/24/87	Japan			Translation No
	JP	63-220411	09/13/88	Japan			Translation No
	JP	7-73429	03/17/95	Japan			Abstract
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
LX		M. Jacobs et al., "Unbalanced Magnetron Sputtered Si-Al Coatings: Plasma Conditions and Film Properties Versus Sample Bias Voltage," 116-119 <u>Surface and Coatings Technology</u> 735-41 (1999).					
		C.D. Adams et al., "Phase Separation During Co-Deposition of Al-Ge Thin Films," 7(3) <u>J. Mater. Res.</u> 653-67 (March 1992).					
		C.D. Adams et al., "Transition from Lateral to Transverse Phase Separation During Film Co-deposition," 59(20) <u>Appl. Phys. Lett.</u> 2535-37 (November 1991).					
		M. Atzmon et al., "Phase Separation During Film Growth," 42(2) <u>J. Appl. Phys.</u> 442-46 (July 1992).					
EXAMINER				DATE CONSIDERED			
LX				9/14/05			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)				ATTY DOCKET NO. 03500.017112		APPLICATION NO. 10/653,978	
				APPLICANT Kazuhiko Fukutani et al.			
				FILING DATE September 4, 2003		GROUP 1775	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
LX		6,027,796	02/22/00	Kondoh et al.	428	312.8	

FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
LX	JP	9-157062	06/17/97	Japan			Translation
↓	JP	2001-261376	09/26/01	Japan			Translation
	WO	03/069677 A1	08/21/03	International			
	WO	03/078685 A1	09/25/03	International			Abstract
↓	JP	2001-101644	04/13/01	Japan			Abstract

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)		
LX		C.D. Adams, et al. "Monte Carlo Simulation of Phase Separation During Thin-Film Codeposition," 74(3) J. Appl. Phys. 1707-15 (August 1993).

EXAMINER <i>Wing Xu</i>	DATE CONSIDERED <i>9/14/05</i>
----------------------------	-----------------------------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 2 of 2